

Lecture 2

Basic Semiconductor Physics

In this lecture you will learn:

- What are semiconductors?
- Basic crystal structure of semiconductors
- Electrons and holes in semiconductors
- Intrinsic semiconductors
- Extrinsic semiconductors
n-doped and p-doped semiconductors

Semiconductors in the Periodic Table

Atomic number

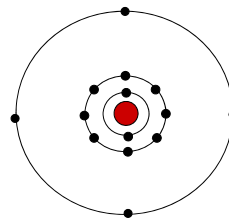
	III A	IV A	V A	VIA
5	B	C	N	O
13	Al	Si	P	S
30	Zn	Ga	Ge	As
48	Cd	In	Sn	Sb

Group IV semiconductors

Each element in group IV has 4 electrons in its outer most atomic shell

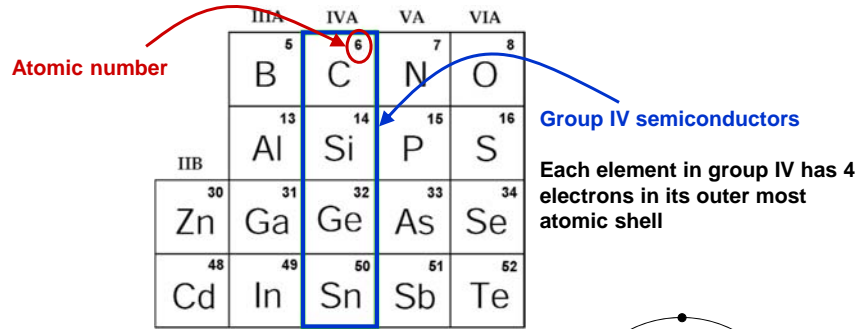
A Silicon atom has:

- 2 electrons in the first atomic shell
- 8 electrons in the second atomic shell
- 4 electrons in the third outermost atomic shell

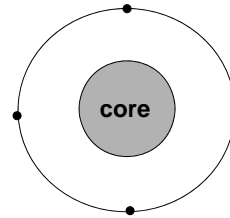


A Silicon atom

Semiconductors in the Periodic Table



- The outermost electrons are called valence electrons
- The inner electrons are called the core electrons



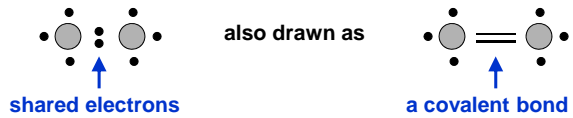
A Silicon atom

Covalent Bonding in Silicon

- A Silicon atom with 4 electrons in the valence shell is drawn in a cartoon way as:

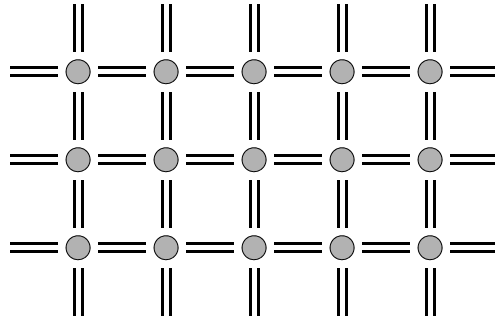


- Two Silicon atoms can come together to form a covalent bond by sharing two electrons among themselves



- Covalent bonding is energetically favorable (i.e. Silicon atoms “like” to form covalent bonds with each other)

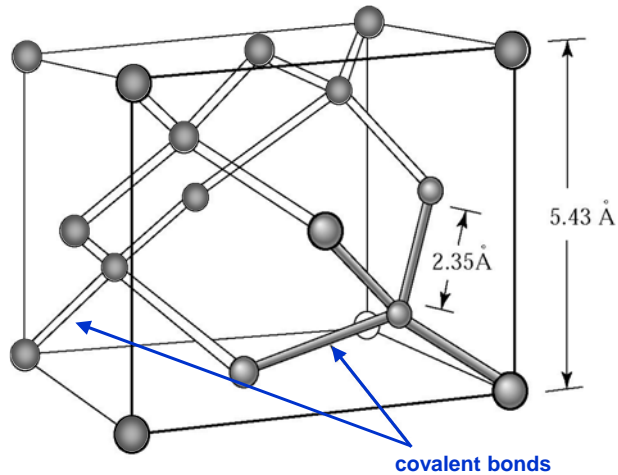
A Silicon Crystal Lattice (A Cartoon View)



In a Silicon crystal:

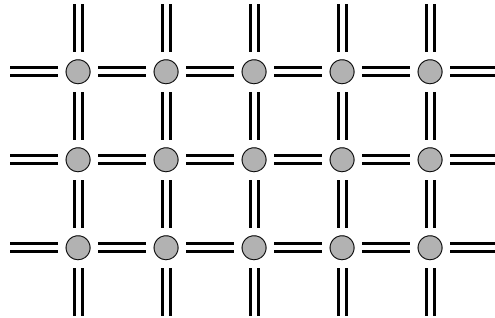
- Each Silicon atom is surrounded by 4 other Silicon atoms
- Each Silicon atom forms 4 covalent bonds with the neighboring Silicon atoms

Actual 3D Structure of a Silicon Crystal Lattice



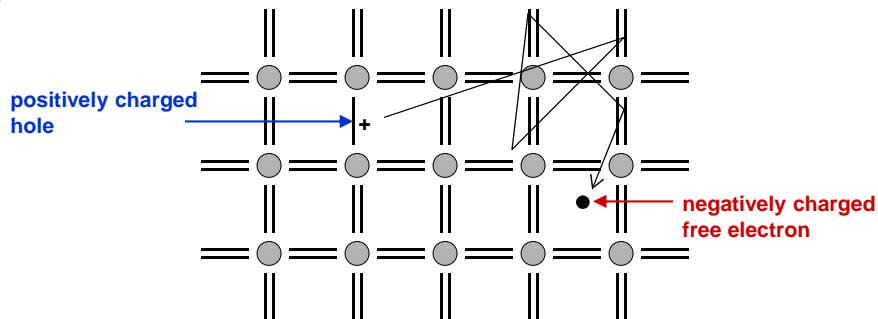
- Each Silicon atom is surrounded by 4 other Silicon atoms in a tetrahedral configuration
- Silicon atomic density = $5 \times 10^{22} \text{ cm}^{-3}$

Electrons and Holes in Semiconductors - I



A perfect Silicon crystal lattice

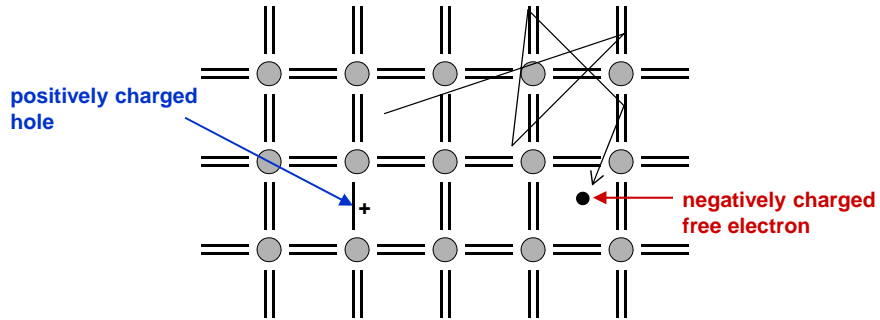
Electrons and Holes in Semiconductors - II



A Silicon crystal lattice with one broken bond

- It requires energy to break a covalent bond
- The required energy is called the “**bandgap**” (bandgap of Silicon is ~1.12 eV)
- A broken bond results in one negatively charged “free electron” and one positively charged “hole”
- The “free electron” can freely move around in the crystal

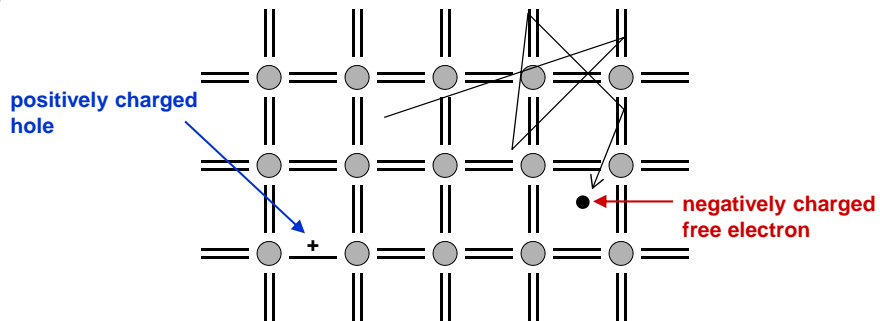
Electrons and Holes in Semiconductors - III



A Silicon crystal lattice with one broken bond

- A hole can also move through the lattice !!
- A hole moves when an electron from a neighboring bond jumps over to fill that "hole"

Electrons and Holes in Semiconductors - III



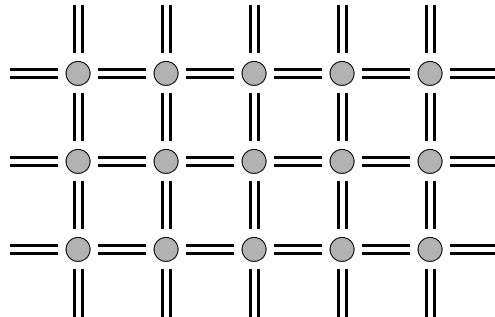
A Silicon crystal lattice with one broken bond

- A hole can also move through the lattice !!
- A hole moves when an electron from a neighboring bond jumps over to fill that "hole"

Definitions and Notations Used in ECE 3150

- The word electron will usually mean a “free electron” (and not an electron forming the covalent bond or a core electron)
 - The electron density is denoted by: n (units: $1/\text{cm}^3$)
 - The hole density is denoted by: p (units: $1/\text{cm}^3$)
 - The charge of an electron is: $-q$
 - The charge of a hole is: $+q$
- $q = 1.6 \times 10^{-19}$ Coulombs

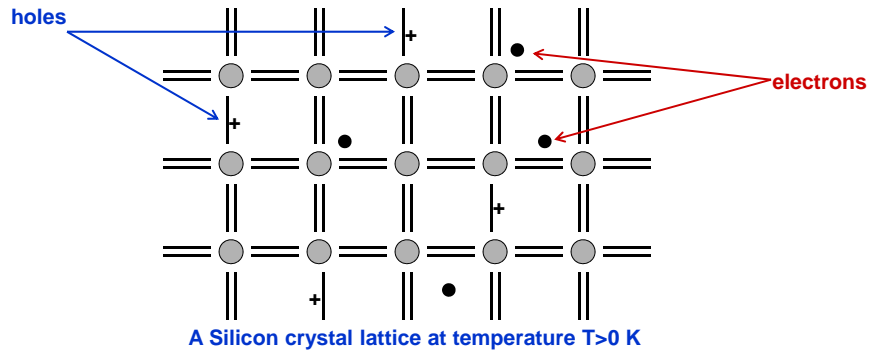
Electrons and Holes at Near Zero Temperature



A perfect Silicon crystal lattice at temperature $T \approx 0$ K

- There are no broken bonds and no electrons and holes (i.e. $n = p = 0$)

Electrons and Holes at Nonzero Temperature



- Thermal energy breaks the covalent bonds and electron-hole pairs are generated (remember it takes energy to break a covalent bond)
- The number of electrons and holes generated are equal - for every electron generated there is also a hole generated (i.e. $n = p$)
- Question: what is the electron and hole density at room temperature?

Thermal Energy

Thermal energy is typically measured in units of “ KT ”

“ K ” is the Boltzmann’s constant and equals $\sim 1.38 \times 10^{-23}$ Joules/Kelvin

Temperature “ T ” is measured in degrees Kelvin

Room temperature corresponds to $T = 300$ K

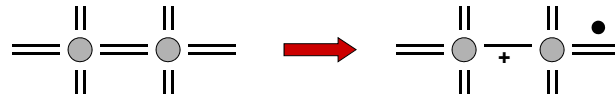
Room temperature corresponds to a “ KT ” value of 4.14×10^{-21} Joules or 25.8 meV

$$\text{Energy in eV} = \frac{\text{Energy in Joules}}{\text{Electron charge in Coulombs}}$$

Generation and Recombination in Semiconductors - I

Generation:

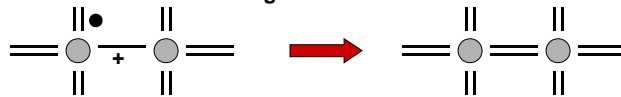
The breaking of a bond to generate an electron-hole pair is called generation



- Generation rate $G(T)$ is a function of temperature
- Units of $G(T)$ are: $\text{cm}^{-3}\cdot\text{s}^{-1}$

Recombination:

An electron can also combine with a hole to form a bond. This process is called recombination. It is the reverse of generation.



- Recombination rate $R(T)$ is proportional to the product np

$$R(T) \propto np \quad \Rightarrow \quad R(T) = k(T) np$$

(you need electrons as well as holes for recombination to happen)

- Units of $R(T)$ are also: $\text{cm}^{-3}\cdot\text{s}^{-1}$

Generation and Recombination in Semiconductors - II

Condition of Thermal Equilibrium:

- In thermal equilibrium a steady state exists in which the rate of electron-hole generation is equal to the rate of electron-hole recombination,

$$\left. \begin{aligned} R(T) &= G(T) \\ \Rightarrow k(T)n_o p_o &= G(T) \\ \Rightarrow n_o p_o &= \frac{G(T)}{k(T)} \end{aligned} \right\} \begin{array}{l} \text{thermal equilibrium electron and hole} \\ \text{densities are usually denoted by } n_o \\ \text{and } p_o \end{array}$$

- By convention, the ratio $\frac{G(T)}{k(T)}$ is written as $n_i^2(T)$
- Therefore, in thermal equilibrium, $n_o p_o = n_i^2(T)$
- Since equal number of electrons and holes are present in thermal equilibrium, we have, $n_o = p_o = n_i(T)$
- n_i is called the “intrinsic” carrier density. It equals the number of electrons (or holes) present in a pure semiconductor in equilibrium at a given temperature.
- For Silicon, $n_i \approx 1 \times 10^{10} \text{ cm}^{-3}$ at room temperature (i.e. at $T = 300\text{K}$)

Doping in Semiconductors

Doping:

The introduction of certain impurity atoms in a pure semiconductor to control its electronic properties is called doping

- Doping is done by two kinds of impurity atoms:
 - a) Donor atoms
 - b) Acceptor atoms

Donors:

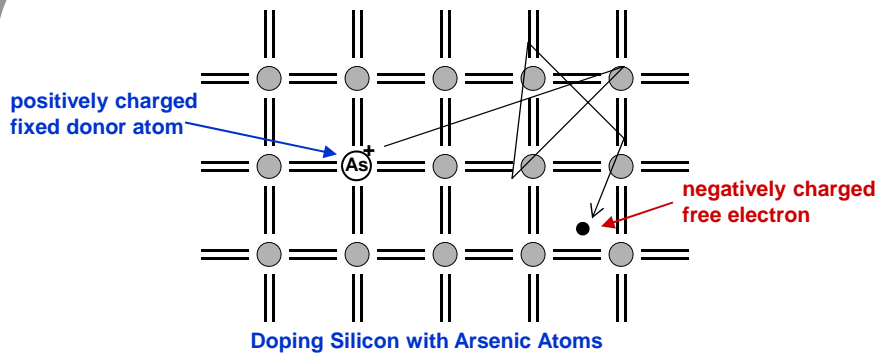
Donor atoms are used to increase the electron density in a semiconductor

	IIIA	IVA	VA	VIA
	5 B	6 C	7 N	8 O
	13 Al	14 Si	15 P	16 S
IIB	30 Zn	31 Ga	32 Ge	33 As
	48 Cd	49 In	50 Sn	51 Sb

• Group V elements have 5 electrons in their outermost atomic shell (one more than group IV atoms)

• Group V elements can act as electron "donors" in Silicon

Doping by Donors in Silicon (n-doping)



- Donor atom concentration is denoted by: N_d (units: $1/\text{cm}^3$)
- Each donor atom contributes one free electron to the crystal
- Donor atom after giving off an electron becomes positively charged

Doping in Semiconductors

Acceptors:

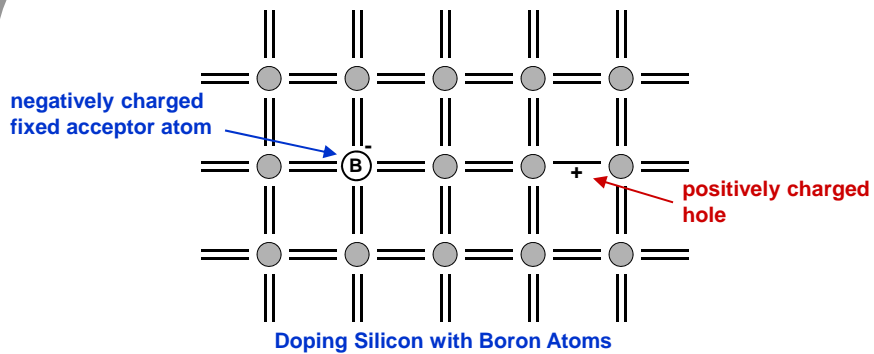
Acceptor atoms are used to increase the hole density in a semiconductor

	III A	IV A	V A	V I A
	B ⁵	C ⁶	N ⁷	O ⁸
	Al ¹³	Si ¹⁴	P ¹⁵	S ¹⁶
II B				
	Zn ³⁰	Ga ³¹	Ge ³²	As ³³
	Cd ⁴⁸	In ⁴⁹	Sn ⁵⁰	Sb ⁵¹
			Te ⁵²	

- Group III elements have 3 electrons in their outermost atomic shell (one less than group IV atoms)

- Group III elements can act as electron "Acceptors" in Silicon

Doping by Acceptors in Silicon (p-doping)



- Acceptor atom concentration is denoted by: N_a (units: $1/\text{cm}^3$)

- Each acceptor atom contributes one hole to the crystal by "accepting" one electron from a neighboring bond

- Acceptor atom after giving off a hole (or equivalently, after accepting an electron) becomes negatively charged

Electron-Hole Density in Doped Semiconductors

Consider a N-doped semiconductor in thermal equilibrium:

Doping density = N_d

• Use condition of charge neutrality: $q(+N_d - n_o + p_o) = 0$

• Together with the relation: $n_o p_o = n_i^2$

• To obtain:

$$n_o = \frac{N_d}{2} + \sqrt{\left(\frac{N_d}{2}\right)^2 + n_i^2}$$

$$p_o = -\frac{N_d}{2} + \sqrt{\left(\frac{N_d}{2}\right)^2 + n_i^2}$$

• If $N_d \gg n_i$, which is usually the case for N-doping, then the above relations simplify:

$$\left. \begin{aligned} n_o &\approx N_d \\ p_o &\approx \frac{n_i^2}{N_d} \end{aligned} \right\}$$

n-doping lets one make the electron density much greater than the intrinsic value n_i

Electron-Hole Density in Doped Semiconductors

Now consider a P-doped semiconductor in thermal equilibrium:

Doping density = N_a

• Use condition of charge neutrality: $q(-N_a - n_o + p_o) = 0$

• Together with the relation: $n_o p_o = n_i^2$

• To obtain:

$$p_o = \frac{N_a}{2} + \sqrt{\left(\frac{N_a}{2}\right)^2 + n_i^2}$$

$$n_o = -\frac{N_a}{2} + \sqrt{\left(\frac{N_a}{2}\right)^2 + n_i^2}$$

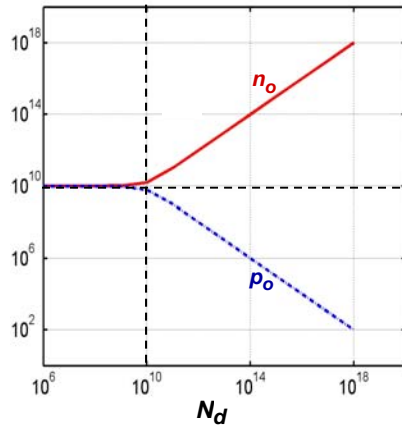
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$$\left. \begin{aligned} p_o &\approx N_a \\ n_o &\approx \frac{n_i^2}{N_a} \end{aligned} \right\}$$

p-doping lets one make the hole density much greater than the intrinsic value n_i

Electron-Hole Density Vs Doping Density

N-doped semiconductors



- With increasing N-doping the electron density increases above the intrinsic value and the hole density decreases below the intrinsic value

Example:

Suppose

$$N_d = 10^{17} \text{ cm}^{-3} \quad \text{and} \quad n_i = 10^{10} \text{ cm}^{-3}$$

then

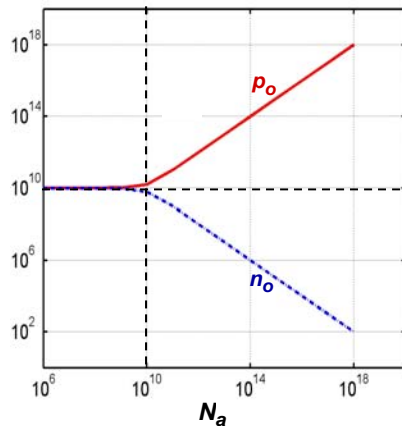
$$n_o \approx 10^{17} \text{ cm}^{-3} \quad (\text{Since } N_d \gg n_i)$$

and

$$p_o = \frac{n_i^2}{n_o} \approx 10^3 \text{ cm}^{-3}$$

Electron-Hole Density Vs Doping Density

P-doped semiconductors



- With increasing P-doping the hole density increases above the intrinsic value and the electron density decreases below the intrinsic value

Example:

Suppose

$$N_a = 10^{17} \text{ cm}^{-3} \quad \text{and} \quad n_i = 10^{10} \text{ cm}^{-3}$$

then

$$p_o \approx 10^{17} \text{ cm}^{-3} \quad (\text{Since } N_a \gg n_i)$$

and

$$n_o = \frac{n_i^2}{p_o} \approx 10^3 \text{ cm}^{-3}$$

Compound Semiconductors

	IIIA	IVA	VA	VIA
	B 5	C 6	N 7	O 8
	Al 13	Si 14	P 15	S 16
IIIB	Zn 30	Ga 31	Ge 32	As 33
	Cd 48	In 49	Sn 50	Sb 51
		Te 52		

III-V semiconductors:

Elements in group III can be combined with elements in group V to give compound semiconductors (as opposed to elemental semiconductors of group IV)

*One can also have II-VI semiconductors

